

10771553\_CLS

Most Frequently Occurring Classifications of Patents Returned  
From A Search of 10771553 on May 27, 2004

Original Classifications

17	250/288
5	204/452
5	210/198.2
3	204/453
3	216/2
3	250/281
2	204/451
2	204/603
2	210/656
2	216/79

Cross-Reference Classifications

20	250/288
14	250/281
14	250/282
10	210/748
9	210/243
8	204/603
7	204/600
7	204/601
7	210/198.2
7	210/656
5	250/423R
5	438/743
4	204/452
4	204/604
4	438/723
3	216/67
3	216/79
3	250/292
3	436/161
3	438/734
3	438/736
3	438/942
2	204/450
2	204/451
2	216/39
2	216/47
2	216/80
2	422/70
2	436/173
2	436/174
2	436/177

2 436/86  
2 436/87  
2 436/89  
2 436/91  
2 436/93  
2 436/94  
2 438/756

Combined Classifications

37 250/288  
17 250/281  
14 250/282  
12 210/198.2  
10 204/603  
10 210/748  
9 204/452  
9 210/243  
9 210/656  
8 204/601  
7 204/600  
5 216/79  
5 250/423R  
5 438/743  
4 204/451  
4 204/453  
4 204/604  
4 438/723  
3 216/2  
3 216/67  
3 250/292  
3 436/161  
3 436/173  
3 438/734  
3 438/736  
3 438/942  
2 204/450  
2 216/39  
2 216/47  
2 216/80  
2 250/289  
2 422/70  
2 436/174  
2 436/177  
2 436/86  
2 436/87  
2 436/89  
2 436/91  
2 436/93

10771553\_CLS

2 436/94  
2 438/756

10771553\_CLSTITLES  
Titles of Most Frequently Occurring Classifications of Patents Returned  
From A Search of 10771553 on May 27, 2004

37 250/288 (17 OR, 20 XR)  
Class 250 : RADIANT ENERGY  
250/281 IONIC SEPARATION OR ANALYSIS  
250/288 .With sample supply means

17 250/281 (3 OR, 14 XR)  
Class 250 : RADIANT ENERGY  
250/281 IONIC SEPARATION OR ANALYSIS

14 250/282 (0 OR, 14 XR)  
Class 250 : RADIANT ENERGY  
250/281 IONIC SEPARATION OR ANALYSIS  
250/282 .Methods

12 210/198.2 (5 OR, 7 XR)  
Class 210 : LIQUID PURIFICATION OR SEPARATION  
210/198.1 WITH MEANS TO ADD TREATING MATERIAL  
210/198.2 .Chromatography

10 204/603 (2 OR, 8 XR)  
Class 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY  
204/193 APPARATUS  
204/600 .Electrophoretic or electro-osmotic apparatus  
204/601 ..Capillary electrophoresis type  
204/603 ...With detailed detection system (e.g.,  
including a light source and a camera, etc.  
)

10 210/748 (0 OR, 10 XR)  
Class 210 : LIQUID PURIFICATION OR SEPARATION  
210/600 PROCESSES  
210/748 .Utilizing electrical or wave energy (directly  
applied to liquid or material being treated  
)

9 204/452 (5 OR, 4 XR)  
Class 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY  
204/450 .Electrophoresis or electro-osmosis processes  
and electrolyte compositions therefor whe  
n not provided for  
elsewhere  
204/451 ..Capillary electrophoresis

10771553\_CLSTITLES  
204/452 ...With detailed detection

9 210/243 (0 OR, 9 XR)  
Class 210 : LIQUID PURIFICATION OR SEPARATION  
210/243 ELECTRICAL INSULATING OR ELECTRICITY  
DISCHARGING

9 210/656 (2 OR, 7 XR)  
Class 210 : LIQUID PURIFICATION OR SEPARATION  
210/600 PROCESSES  
210/656 .Chromatography

8 204/601 (1 OR, 7 XR)  
Class 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY  
204/193 APPARATUS  
204/600 .Electrophoretic or electro-osmotic apparatus  
204/601 ..Capillary electrophoresis type

7 204/600 (0 OR, 7 XR)  
Class 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY  
204/193 APPARATUS  
204/600 .Electrophoretic or electro-osmotic apparatus

5 216/79 (2 OR, 3 XR)  
Class 216 : ETCHING A SUBSTRATE: PROCESSES  
216/58 GAS PHASE ETCHING OF SUBSTRATE  
216/74 .Etching inorganic substrate  
216/79 ..Etching silicon containing substrate

5 250/423R (0 OR, 5 XR)  
Class 250 : RADIANT ENERGY  
250/423R ION GENERATION

5 438/743 (0 OR, 5 XR)  
Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS  
438/689 CHEMICAL ETCHING  
438/706 .Vapor phase etching (i.e., dry etching)  
438/735 ..Differential etching of semiconductor  
substrate  
438/737 ...Substrate possessing multiple layers  
438/743 ....Silicon oxide or glass

4 204/451 (2 OR, 2 XR)  
Class 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY  
204/450 .Electrophoresis or electro-osmosis processes

10771553\_CLSTITLES  
and electrolyte compositions therefor when

not provided for

elsewhere

..Capillary electrophoresis

4 204/453 (3 OR, 1 XR)

Class 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY

204/450 .Electrophoresis or electro-osmosis processes  
and electrolyte compositions therefor whe

n not provided for

elsewhere

204/451 ..Capillary electrophoresis

204/453 ...With injection

4 204/604 (0 OR, 4 XR)

Class 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY

204/193 APPARATUS

204/600 .Electrophoretic or electro-osmotic apparatus

204/601 ..Capillary electrophoresis type

204/604 ...With injector

4 438/723 (0 OR, 4 XR)

Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/689 CHEMICAL ETCHING

438/706 .Vapor phase etching (i.e., dry etching)

438/707 ..Utilizing electromagnetic or wave energy

438/710 ...By creating electric field (e.g., plasma,  
glow discharge, etc.)

438/723 ....Silicon oxide or glass

3 216/2 (3 OR, 0 XR)

Class 216 : ETCHING A SUBSTRATE: PROCESSES

216/2 ETCHING OF SEMICONDUCTOR MATERIAL TO PRODUCE A

N

ARTICLE HAVING A NONELECTRICAL FUNCTION

3 216/67 (0 OR, 3 XR)

Class 216 : ETCHING A SUBSTRATE: PROCESSES

216/58 GAS PHASE ETCHING OF SUBSTRATE

216/63 .Application of energy to the gaseous etchant  
or to the substrate being etched

216/67 ..Using plasma

3 250/292 (0 OR, 3 XR)

Class 250 : RADIANT ENERGY

250/281 IONIC SEPARATION OR ANALYSIS

10771553\_CLSTITLES

250/290 .Cyclically varying ion selecting field means

250/292 ..Laterally resonant ion path

3 436/161 (0 OR, 3 XR)  
Class 436 : CHEMISTRY: ANALYTICAL AND IMMUNOLOGICAL  
TESTING  
436/161 INCLUDING CHROMATOGRAPHY

3 436/173 (1 OR, 2 XR)  
Class 436 : CHEMISTRY: ANALYTICAL AND IMMUNOLOGICAL  
TESTING  
436/173 NUCLEAR MAGNETIC RESONANCE, ELECTRON SPIN  
RESONANCE OR OTHER SPIN EFFECTS OR MASS SPE  
CTROMETRY

3 438/734 (0 OR, 3 XR)  
Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS  
  
438/689 CHEMICAL ETCHING  
438/706 .Vapor phase etching (i.e., dry etching)  
438/734 ..Sequential etching steps on a single layer

3 438/736 (0 OR, 3 XR)  
Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS  
  
438/689 CHEMICAL ETCHING  
438/706 .Vapor phase etching (i.e., dry etching)  
438/735 ..Differential etching of semiconductor  
substrate  
438/736 ...Utilizing multilayered mask

3 438/942 (0 OR, 3 XR)  
Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS  
  
438/942 MASKING

2 204/450 (0 OR, 2 XR)  
Class 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY  
204/450 .Electrophoresis or electro-osmosis processes  
and electrolyte compositions therefor when  
not provided for  
elsewhere

2 216/39 (0 OR, 2 XR)  
Class 216 : ETCHING A SUBSTRATE: PROCESSES  
216/39 FORMING GROOVE OR HOLE IN A SUBSTRATE WHICH IS  
SUBSEQUENTLY FILLED OR COATED

10771553\_CLSTITLES

2 216/47 (0 OR, 2 XR)  
Class 216 : ETCHING A SUBSTRATE: PROCESSES  
216/41 MASKING OF A SUBSTRATE USING MATERIAL RESISTAN  
T  
TO AN ETCHEANT (I.E., ETCHE RESIST)  
216/47 .Mask is multilayer resist

2 216/80 (0 OR, 2 XR)  
Class 216 : ETCHING A SUBSTRATE: PROCESSES  
216/58 GAS PHASE ETCHING OF SUBSTRATE  
216/74 .Etching inorganic substrate  
216/79 ..Etching silicon containing substrate  
216/80 ...Silicon containing substrate is glass

2 250/289 (1 OR, 1 XR)  
Class 250 : RADIANT ENERGY  
250/281 IONIC SEPARATION OR ANALYSIS  
250/289 .With evacuation or sealing means

2 422/70 (0 OR, 2 XR)  
Class 422 : CHEMICAL APPARATUS AND PROCESS DISINFECTING,  
DEODORIZING, PRESERVING, OR STERILIZING  
422/50 ANALYZER, STRUCTURED INDICATOR, OR MANIPULATIV  
E  
LABORATORY DEVICE  
422/68.1 .Means for analyzing liquid or solid sample  
422/69 ..Sorption testing  
422/70 ...Liquid chromatography

2 436/174 (0 OR, 2 XR)  
Class 436 : CHEMISTRY: ANALYTICAL AND IMMUNOLOGICAL  
TESTING  
436/174 INCLUDING SAMPLE PREPARATION

2 436/177 (0 OR, 2 XR)  
Class 436 : CHEMISTRY: ANALYTICAL AND IMMUNOLOGICAL  
TESTING  
436/174 INCLUDING SAMPLE PREPARATION  
436/177 .Liberation or purification of sample or  
separation of material from a sample (e.g.,  
filtering,  
centrifuging, etc.)

2 436/86 (0 OR, 2 XR)  
Class 436 : CHEMISTRY: ANALYTICAL AND IMMUNOLOGICAL  
TESTING  
436/86 PEPTIDE, PROTEIN OR AMINO ACID

10771553\_CLSTITLES

2 436/87 (0 OR, 2 XR)  
Class 436 : CHEMISTRY: ANALYTICAL AND IMMUNOLOGICAL  
TESTING  
436/86 PEPTIDE, PROTEIN OR AMINO ACID  
436/87 .Glycoproteins (e.g., hormone, etc.)

2 436/89 (0 OR, 2 XR)  
Class 436 : CHEMISTRY: ANALYTICAL AND IMMUNOLOGICAL  
TESTING  
436/86 PEPTIDE, PROTEIN OR AMINO ACID  
436/89 .Amino acid or sequencing procedure

2 436/91 (0 OR, 2 XR)  
Class 436 : CHEMISTRY: ANALYTICAL AND IMMUNOLOGICAL  
TESTING  
436/91 HETEROCYCLIC CARBON COMPOUND (I.E., O, S, N,  
Se, Te, AS ONLY RING HETERO ATOM)

2 436/93 (0 OR, 2 XR)  
Class 436 : CHEMISTRY: ANALYTICAL AND IMMUNOLOGICAL  
TESTING  
436/91 HETEROCYCLIC CARBON COMPOUND (I.E., O, S, N,  
Se, Te, AS ONLY RING HETERO ATOM)  
436/93 .Hetero-O (e.g., ascorbic acid, etc.)

2 436/94 (0 OR, 2 XR)  
Class 436 : CHEMISTRY: ANALYTICAL AND IMMUNOLOGICAL  
TESTING  
436/91 HETEROCYCLIC CARBON COMPOUND (I.E., O, S, N,  
Se, Te, AS ONLY RING HETERO ATOM)  
436/93 .Hetero-O (e.g., ascorbic acid, etc.)  
436/94 ..Saccharide (e.g., DNA, etc.)

2 438/756 (0 OR, 2 XR)  
Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS  
438/689 CHEMICAL ETCHING  
438/745 .Liquid phase etching  
438/756 ..Silicon oxide